Abstracts

Dispersive Effects of a Thin Metal-Insulating Layer in MMIC Structures

A.C. Polycarpou, M.R. Lyons and C.A. Balanis. "Dispersive Effects of a Thin Metal-Insulating Layer in MMIC Structures." 1996 MTT-S International Microwave Symposium Digest 96.1 (1996 Vol. I [MWSYM]): 303-306.

A full-wave finite element analysis is used to examine the dispersive effects of a thin metal-insulating layer in CPW and microstrip MMICs. This layer is often encountered in the MMIC manufacturing process residing on top of a semiconducting substrate. The effects of metallization thickness are also examined.

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